

Karl Suss MA6/BA6 Contact Aligner



Process Description:

Lithography is a process for optically projecting an image onto a wafer that has been coated with a thin layer of photosensitive material called photoresist. Contact or proximity printing is the simplest lithography method. When UV light passes through the pattern area of a chrome mask, it exposes the photoresist on the wafer and a chemical process occurs. After a developing solution bath and rinse, a pattern is transferred via the remaining photoresist on the wafer. The next process step, such as etching or ion implanting, can then be performed.

Equipment Description:

The MA6/BA6 aligner has holders for 7, 5 and 4-inch masks. The wafer chucks are for 10x10mm pieces up to 6-inch wafers. The aligner is equipped with a 350 watt mercury short-arc lamp. The filtered light source produces a combination of g-line, h-line and i-line wavelengths (350-500nm). With manual operation, the MA6 can provide print structures into the sub-micron region with all contact exposure programs of vacuum, hard, soft, contact and proximity. The MA6 offers optical alignment top of substrate or the bottom of substrate. The split-screen digital monitor allows you to view for top and the bottom of the substrate. Alignment is performed manually by manipulating X, Y and Theta micrometers.